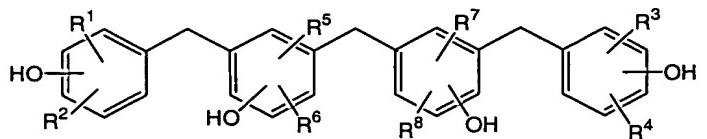


AMENDMENTS TO THE SPECIFICATION

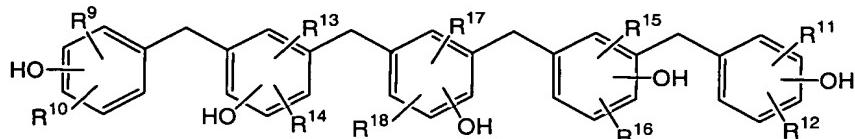
Please replace the paragraph bridging pages 3-5 with the following amended paragraph:

Specifically, the present invention provides a positive photoresist composition including (A) an alkali-soluble resin, (B) a photosensitizer including a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and at least one of a compound represented by following Formula (I):



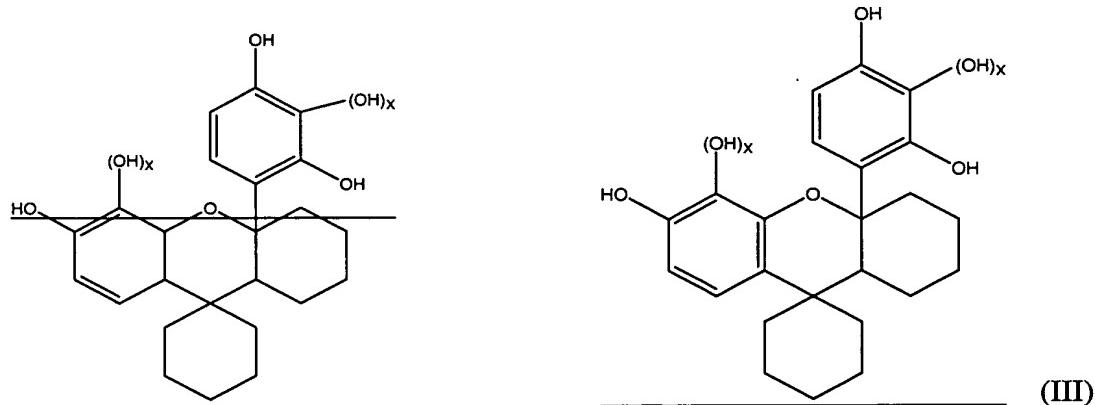
(I)

wherein R¹, R², R³, R⁴, R⁵, R⁶, R⁷ and R⁸ are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and a compound represented by following Formula (II):



(II)

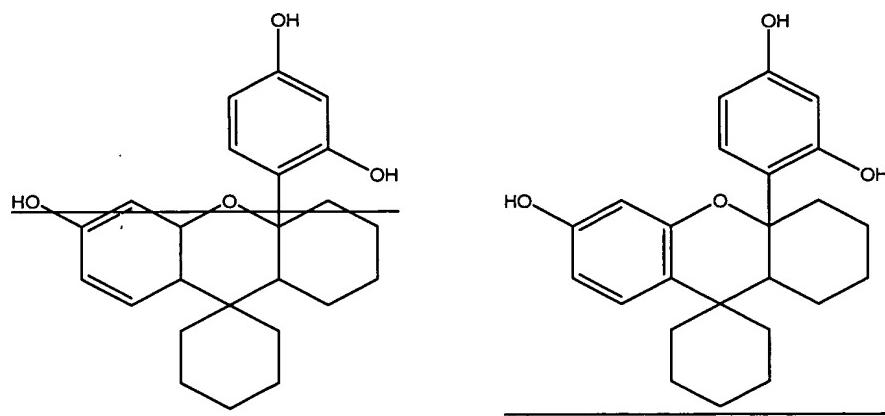
wherein R⁹, R¹⁰, R¹¹, R¹², R¹³, R¹⁴, R¹⁵, R¹⁶, R¹⁷ and R¹⁸ are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group, and (C) a sensitizer including at least one of a compound represented by following Formula (III):



wherein x is 0 or 1.

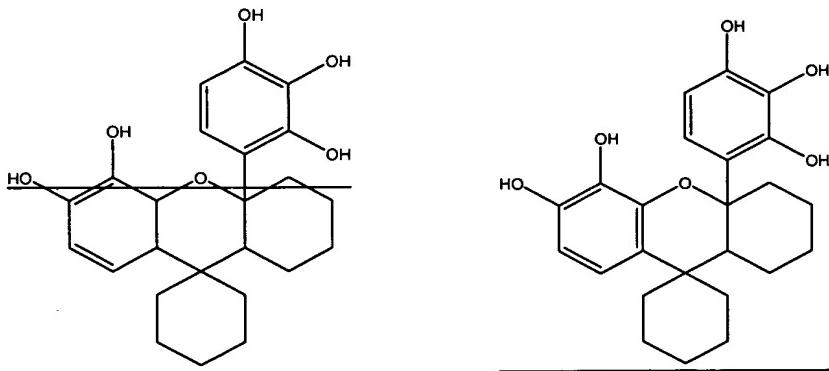
Please replace the second paragraph on page 6 with the following amended paragraph:

The compound represented by Formula (III) is preferably a compound represented by the following formula:



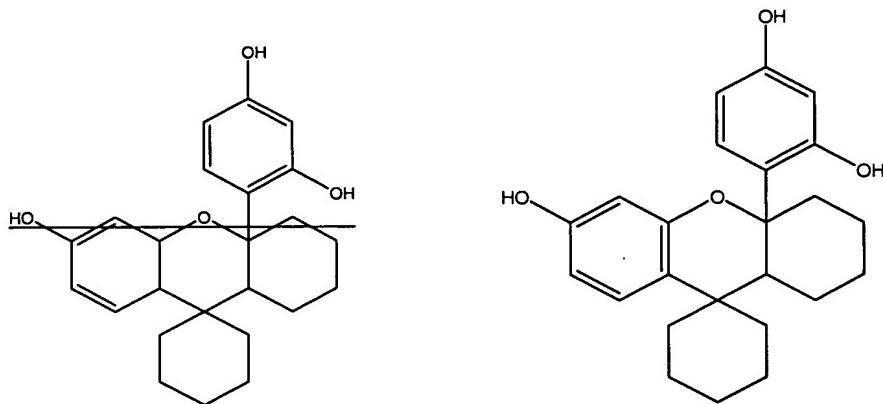
Please replace the paragraph bridging pages 6-7 with the following amended paragraph:

Alternatively, the compound represented by Formula (III) is preferably a compound represented by the following formula:



Please replace the first full paragraph on page 16 with the following amended paragraph:

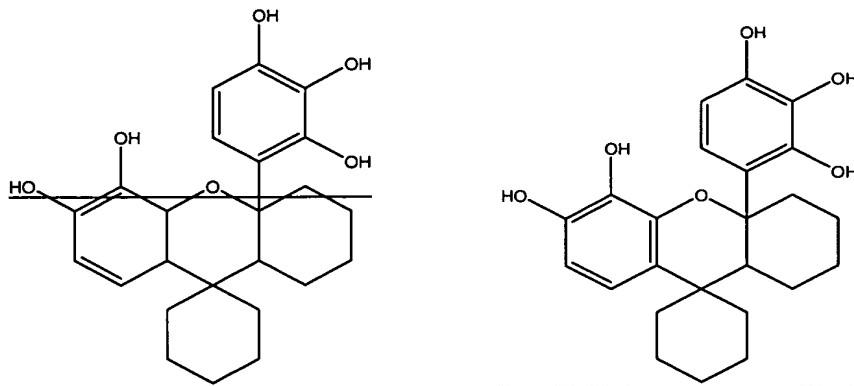
Among the compounds represented by Formula (III) for use as the ingredient (C), typically preferred is a compound represented by the following formula:



By using this compound, the resulting positive photoresist composition has further improved sensitivity and definition and causes less shrink.

Please replace the paragraph bridging pages 16-17 with the following amended paragraph:

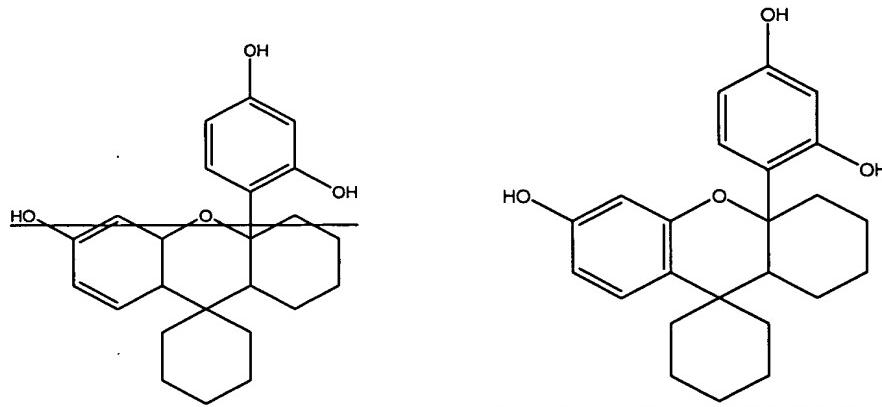
Alternatively, the compound represented by Formula (III) is preferably a compound represented by the following formula:



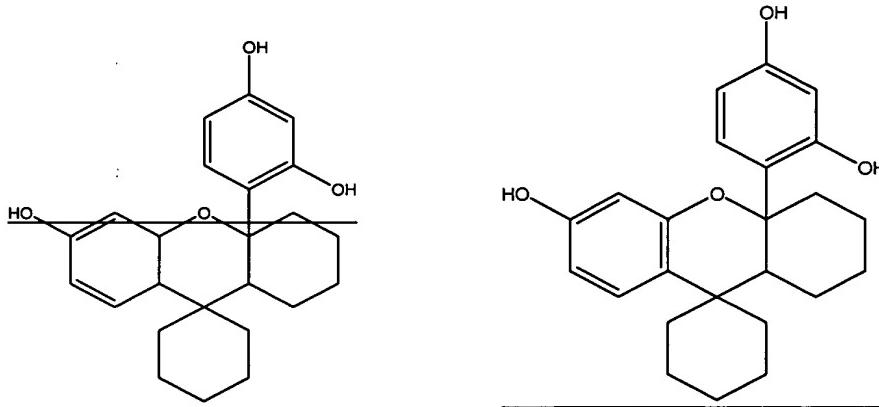
By using this compound, the resulting positive photoresist composition has further improved sensitivity and definition and causes less shrink.

Please replace the first paragraph on page 25 with the following amended paragraph:

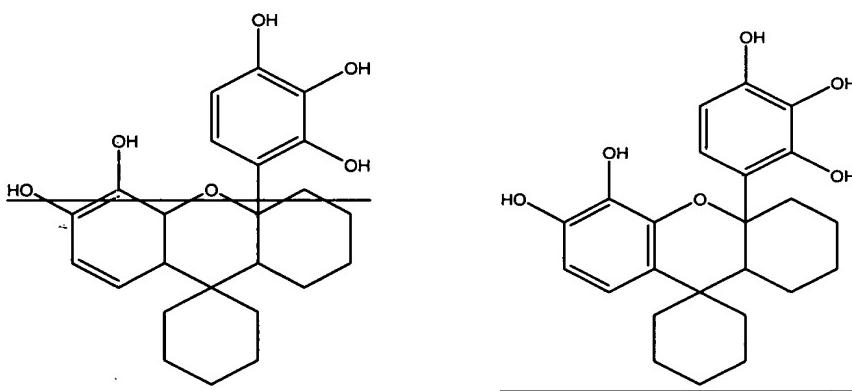
Ingredient C: The following compound (c1):



Please replace the last chemical compound shown on page 28 with the following amended chemical compound:

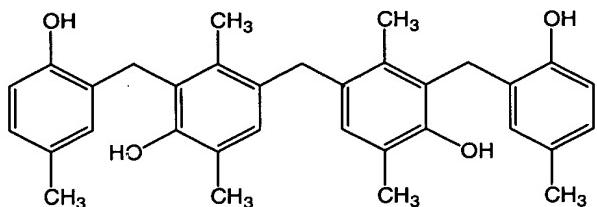


Please replace the first chemical compound shown on page 29 with the following
amended chemical compound:

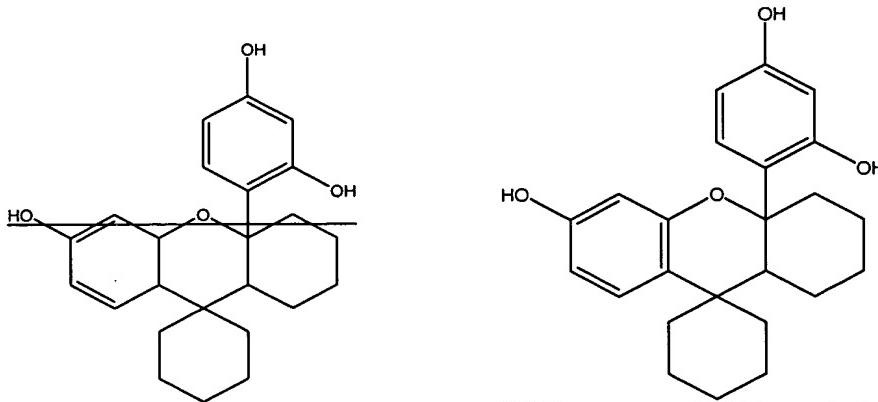


Please replace the present Abstract of the Disclosure with the following amended Abstract of the Disclosure (a replacement Abstract of the Disclosure page to be substituted into the application is attached hereto).

A composition includes (A) an alkali-soluble resin, (B) a quinonediazide ester of a compound represented by the following formula:



and (C) a compound represented by the following formula:



This composition is a positive photoresist composition that is excellent in sensitivity and definition and causes less shrink.